

U.S. Department of Commerce, Patent and Trademark Office

Docket No.: AM-5209.D2

Serial No.: 10/693,775

LIST OF RELEVANT ART CITED BY APPLICANT

Applicant: Ling Chen et al.

(Use several sheets if necessary)

Filing Date: October 24, 2003

Group: ~~Unknown~~ 2813

U.S. PATENT DOCUMENTS

*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
TN	AA	5,770,519	06/23/98	Klein et al.	438	639	—
TN	AB	5,846,332	12/08/98	Zhao et al.	118	728	—
TN	AC	5,933,753	08/03/99	Simon et al.	438	629	—
TN	AD	5,985,762	11/16/99	Geffken et al.	438	687	—
TN	AE	6,106,625	08/22/00	Koai et al.	118	715	—
TN	AF	6,265,313	07/24/01	Huang et al.	438	687	—
TN	AG	6,277,249	08/21/01	Gopalraja et al.	204	192.12	—
TN	AH	6,284,657	09/04/01	Chooi et al.	438	687	—
TN	AI	6,287,977	09/11/01	Hashim et al.	438	722	—
TN	AJ	6,294,458	09/25/01	Zhang et al.	438	627	—
TN	AK	6,306,732	10/23/01	Brown	438	468	—

FOREIGN PATENT DOCUMENTS (Translation)

		Document Number	Date	Country	Class	Subclass	Yes	No
TN	AL	XP-002223600	5/11/2000	Japan	—	—	Abstract	
TN	AM	2000-323571	11/24/00	Japan	—	—	Abstract	

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

TN	AR	Yamagishi et al., "TEM/SEM Investigation and Electrical Evaluation of a Bottomless 1-PVS Ta(N) Barrier in a Dual Mask", <i>Advanced Metallization Conference 2000, Proceedings of the Conference 2000, Advanced Metallization Conference 2000, Proceedings of the Conference, San Diego, CA, USA, October 2-5, 2000, 279-285 pp.</i>						
	AS							
	AT							

Examiner

T. Nguyen

Date Considered

4/21/04

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.